

Fabrication and characterization of wide area SiC detectors for neutron monitoring

Solid State Physics Group

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Y. Garino (PhD Student)

Projects and collaboration

GAMMA-NEU, INFN

G. Wagner, IKZ, Berlin, Germany

C. Lanzieri & S. Lavanga, AMSJV, Rome, Italy

G. Amato & L. Boarino, IEN, Turin, Italy

ENEA (TAPIRO), Casaccia, Rome, Italy

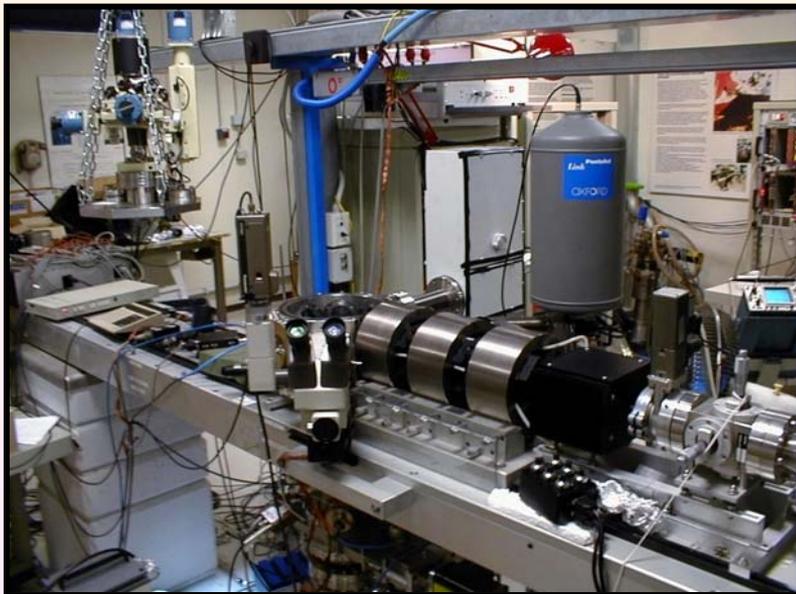
Ion Beam Analysis

AN2000 microbeam facility @
INFN National Laboratories (Legnaro, I)
Dr. Valentino Rigato

2.5 MV Van de Graaff accelerator

available ions: H, He
micrometric spot size

PIXE, IBICC and IBIL measurements
recently developed cryogenic apparatus

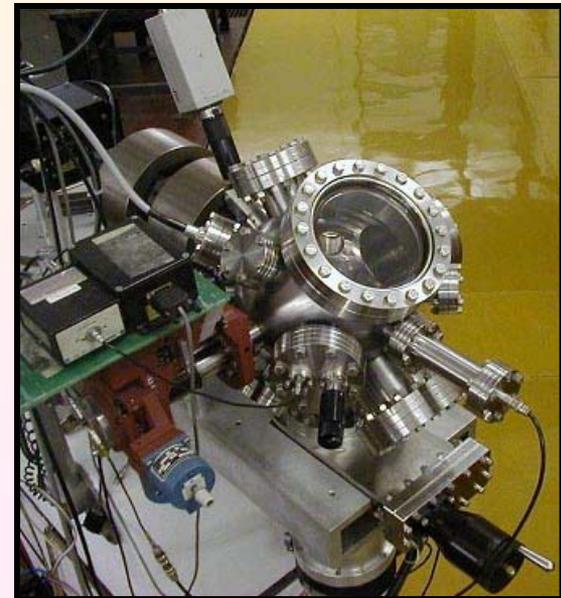


Nuclear microprobe facility @
Ruđer Bošković Institute (Zagreb, Croatia)
Dr. Milko Jaksic

6 MV Tandem accelerator

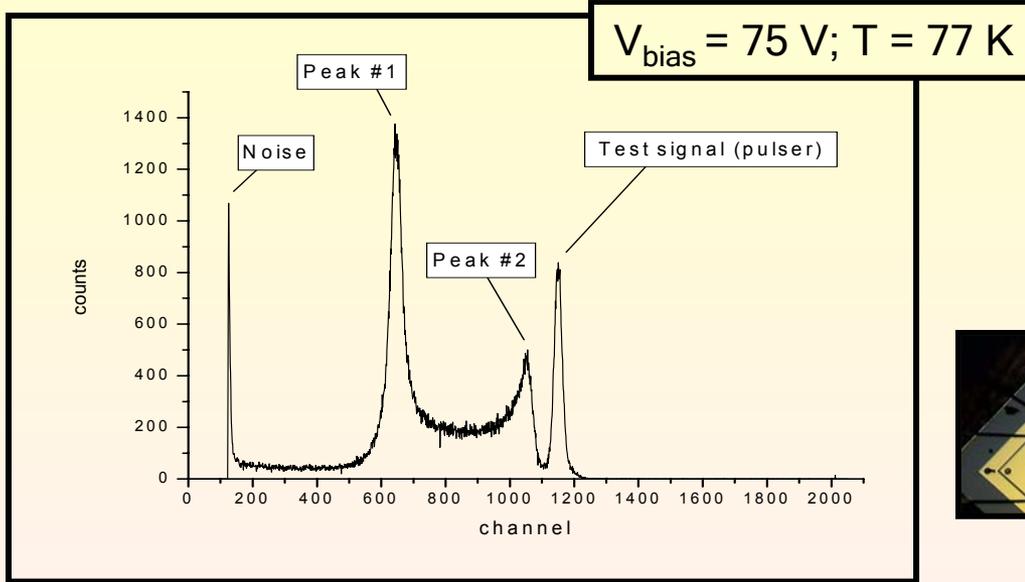
available ions: H, C, Li, O, ...
micrometric spot size

PIXE, IBICC measurements



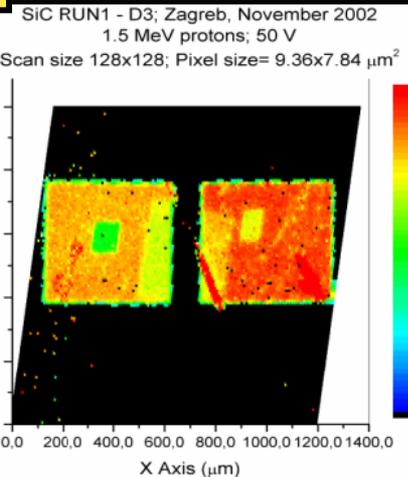
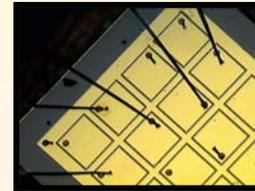
Ion Beam Analysis

4H-SiC IKZ sample; 1.5 MeV protons (Legnaro 2003)



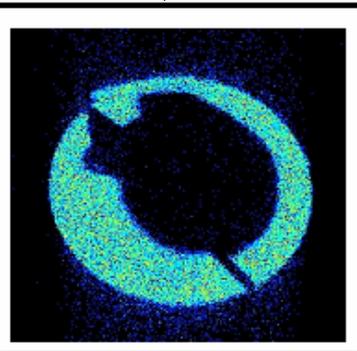
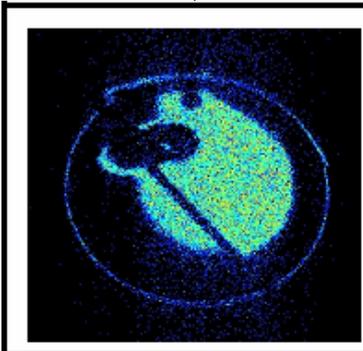
“Silicon Carbide Radiation Detectors for Room and High temperature Spectrometry”, COFIN-MIUR

- G. Bertuccio: Dept Elect Engn & Informat Sci, Politecnico of Milano
- A.Cavallini: Physics Dept., University of Bologna
- F.Nava: Physics Dept., University of Modena
- C.Lanzieri: Alenia Marconi Systems, Roma (I)



Peak #1 map

Peak #2 map

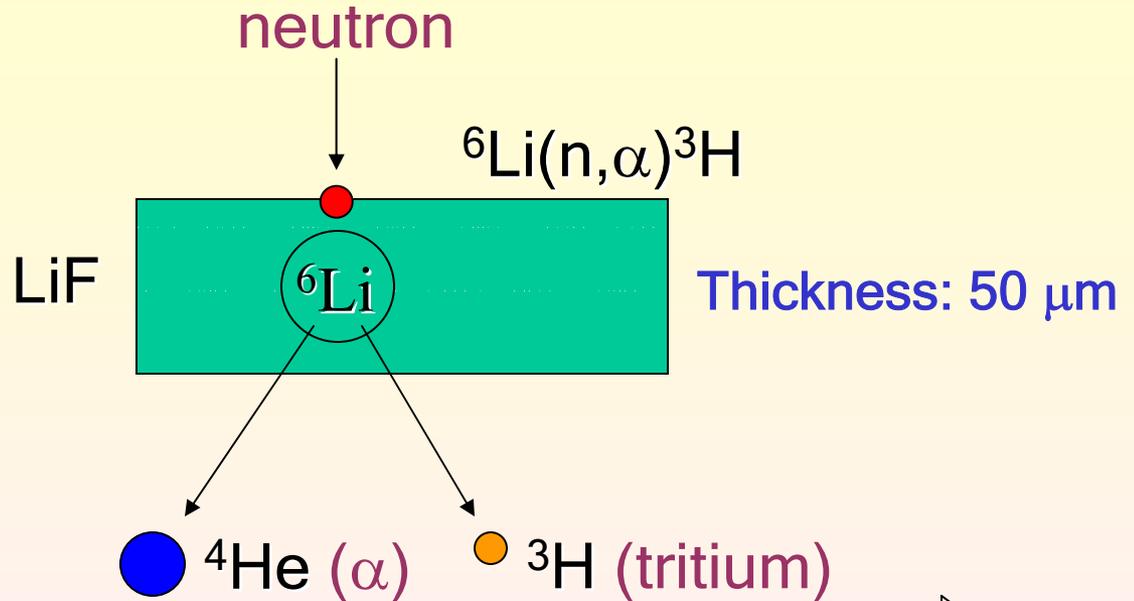
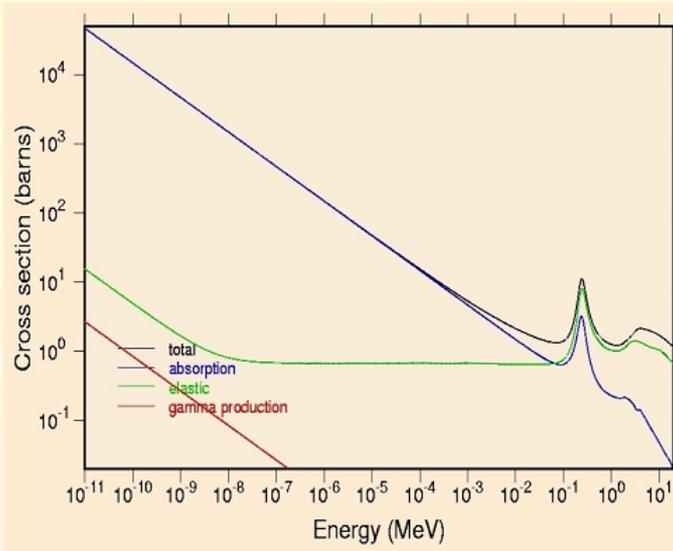


Vittone et al., 2003

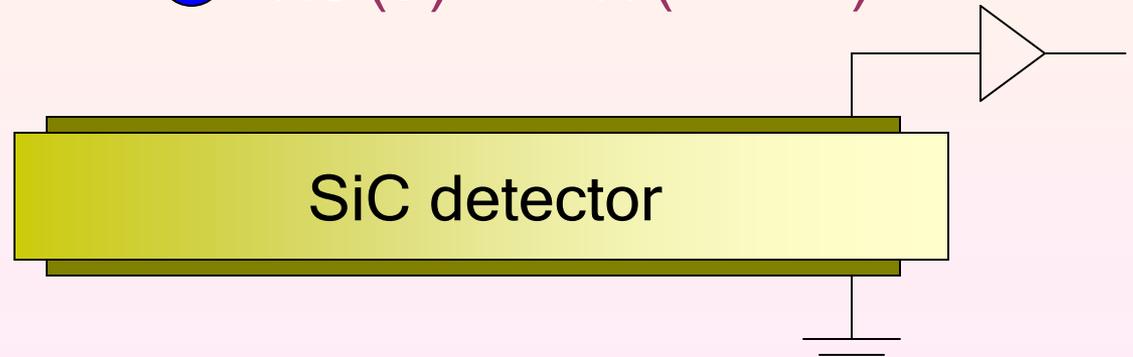
Outline

- About Neutron detector.
- Samples description.
- CV and IV electrical characterization.
- Characterization under exposure to alpha sources.
- Neutron monitoring.
- Conclusions.

Neutron detectors



Detector
Depletion layer > 30 μm



Neutron detectors

Conversion reaction: ${}^6\text{Li}(n,\alpha){}^3\text{H}$

Q-value = 4.78 MeV

For a neutron spectrometer:

mean free path of reaction products within the active volume of the detector

		Neutron Energy [MeV]			
		$2.5 \cdot 10^{-8}$ MeV	0.1 MeV	2 MeV	10 MeV
Alpha	Ion Energy	2.05 MeV	2.35 MeV	4.29 MeV	10.86 MeV
	Penetration in SiC	4.8 μm	5.7 μm	12.6 μm	53.0 μm
Tritium	Ion Energy	2.73 MeV	2.53 MeV	2.49 MeV	3.92 MeV
	Penetration in SiC	27.4 μm	24.4 μm	23.8 μm	48.2 μm

Due to the low deposited energy, gamma background signals can be effectively distinguished from neutron signals, by choosing an appropriate cut-off.

Possible applications of SiC: intense neutron fields (included the case of mixed radiation fields):

1. Fast neutron fields (fusion reactors)
2. Epithermal neutron fields (BNCT facilities) $10^9\text{-}10^{13} \text{ n cm}^{-2} \text{ s}^{-1}$

where a small obstruction, a great radiation hardness and a continuous radiation monitoring are required.

Samples

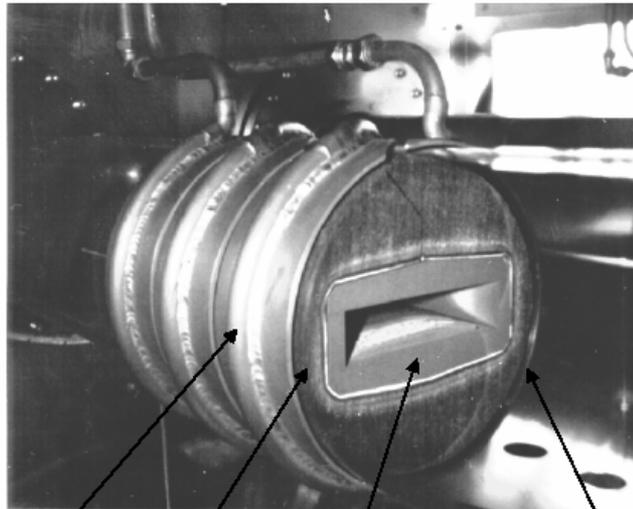
Starting Material: 360 μm n-type 4H-SiC by CREE (USA)

We processed two 2.0 inches wafers (a 3rd wafer is now under processing)

1st wafer: SMP quality: 16-30 micropipes/cm²

2nd wafer: LMP quality: ≤ 15 micropipes/cm²

Epilayer by G. Wagner, Institute of Crystal Growth (IKZ), Berlin, Germany



RF-coil

isolation

susceptor

quartz-tube

Pre-treatment:

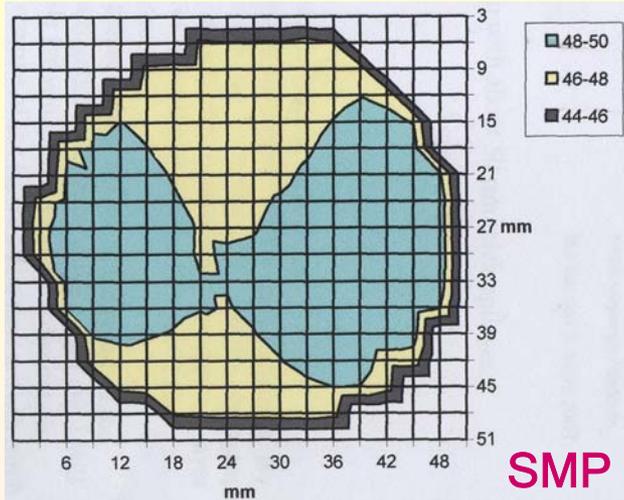
etching by hydrogen/propane gas for 4 minutes, in order to remove the damage layer (about 40 nm).

Growth conditions:

- hot-wall CVD reactor
- temperature: 1550 °C
- total pressure: 150 mbar
- C/Si ratio: 1.5
- growth rate: 9.5 $\mu\text{m}/\text{h}$
- nitrogen partial pressure: 2×10^{-4} mbar

Samples

Epilayer by G. Wagner, Institute of Crystal Growth (IKZ), Berlin, Germany

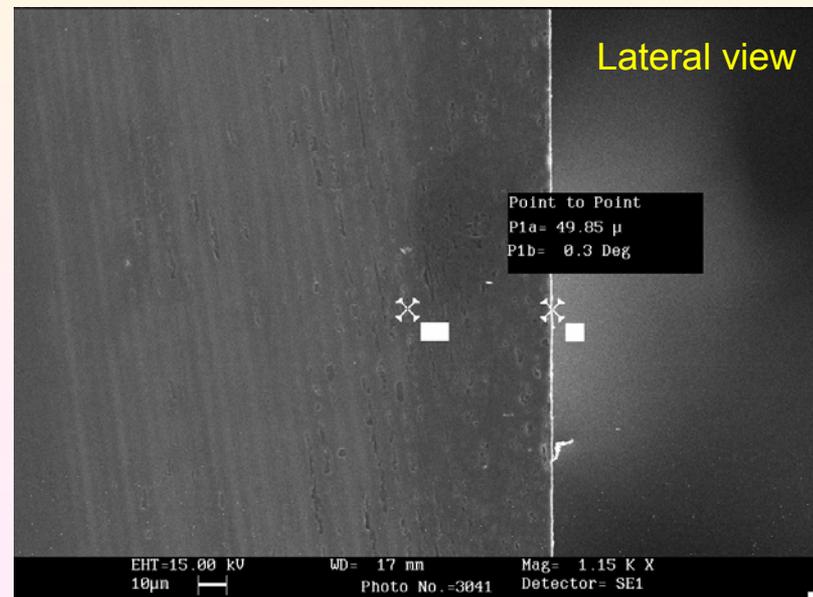
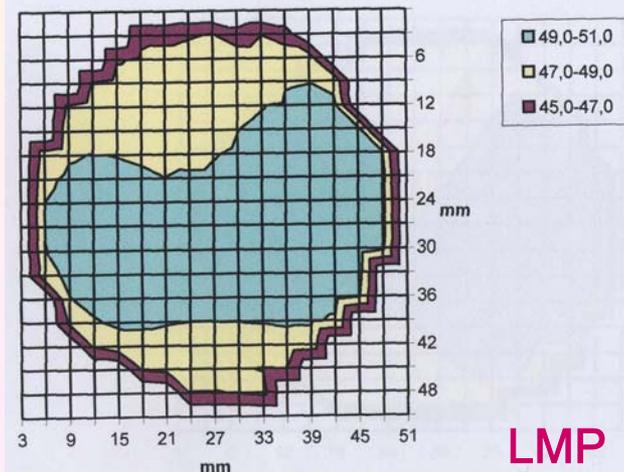


SMP wafer

Epilayer thickness: $48.0 \pm 0.6 \mu\text{m}$

LMP wafer

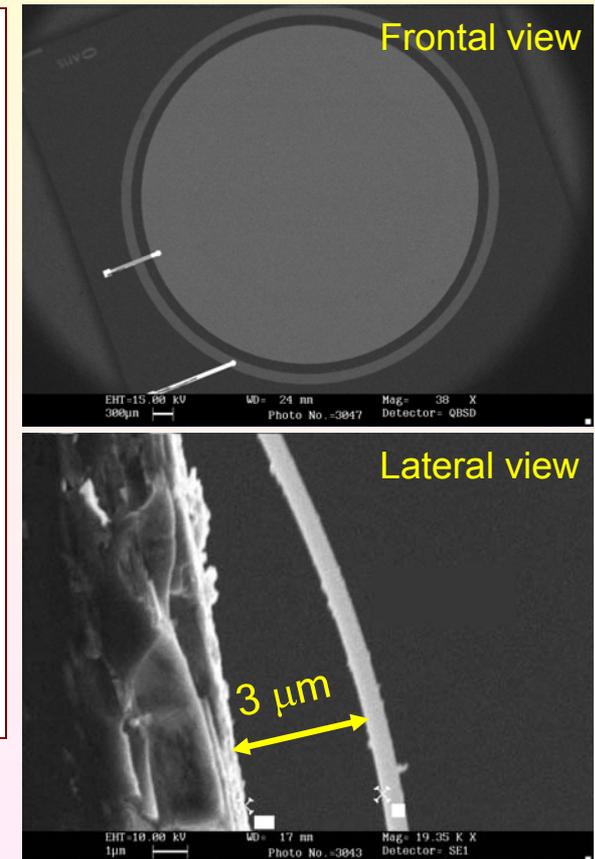
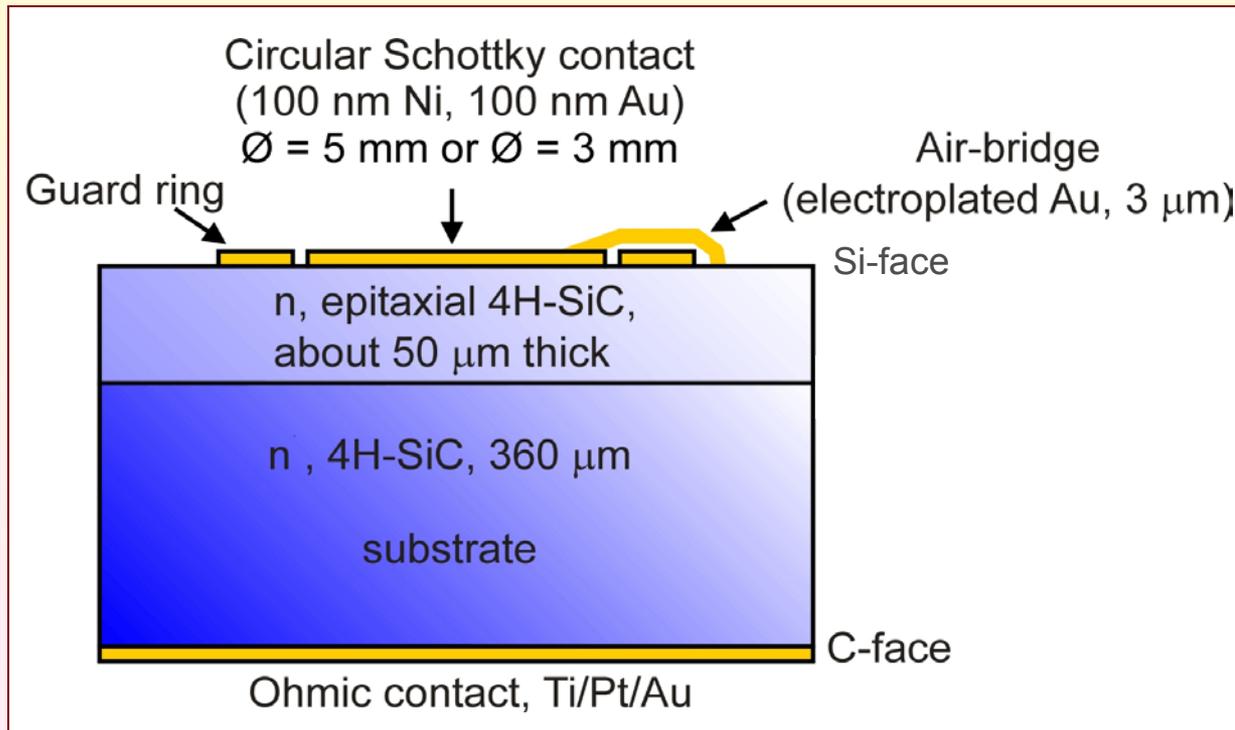
Epilayer thickness: $48.9 \pm 0.8 \mu\text{m}$



Samples

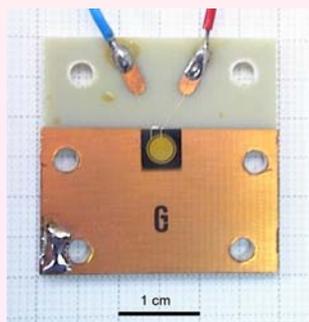
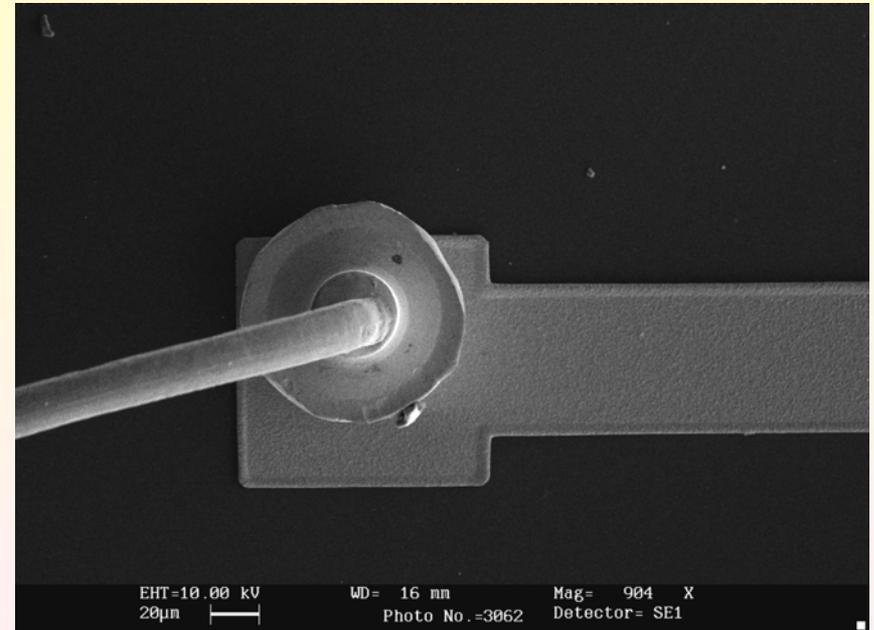
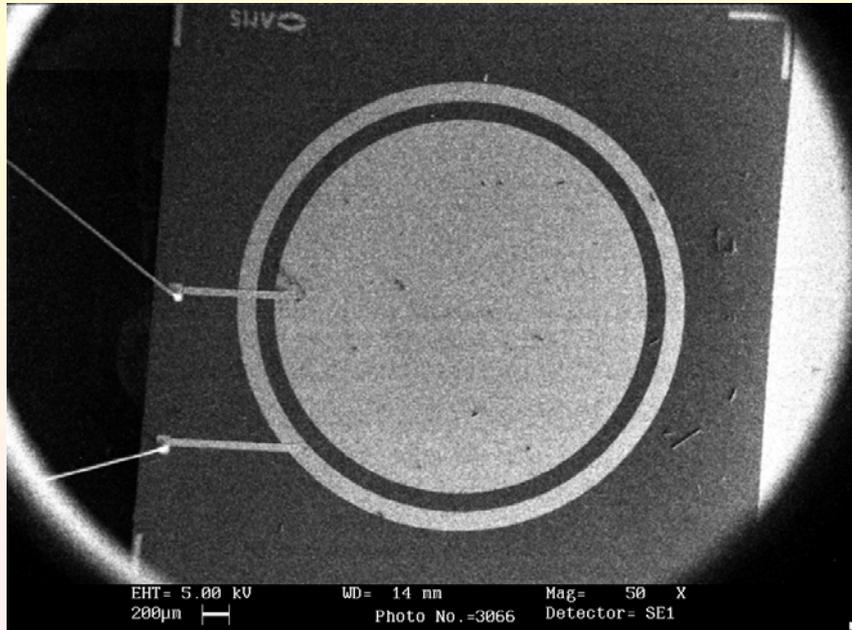
Devices by C. Lanzieri, Alenia Marconi System JV (AMSJV), Rome, Italy

Using a mask designed for our purposes, Alenia produced “small” (3 mm diameter) and large (5 mm diameter) Schottky SiC diodes. Up to now only 1.5 mm.



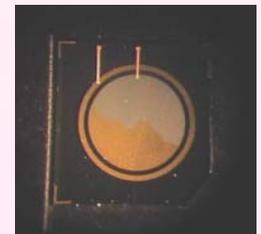
Samples

Microbonds by G. Amato, Istituto Elettrotecnico Nazionale Galileo Ferraris (IEN), Turin, Italy



Devices were then ready for tests.

At now we have 20 small ($\varnothing = 3$ mm) diodes and 3 large diodes ($\varnothing = 5$ mm) from SMP wafer
20 small diodes ($\varnothing = 3$ mm) and 10 large diodes ($\varnothing = 5$ mm) from LMP wafer.



I-V and C-V characterization

Our set-up



Voltage Source Keithley 617: -2 / +100 Volt
Stanford PS350: +30 / +350 Volt

Picoamperometer Keithley 617

Capacimeter Bontoon BD52

When possible, to standardize measurements we used recommendation for Si diode measurements by A. Chilingarov.

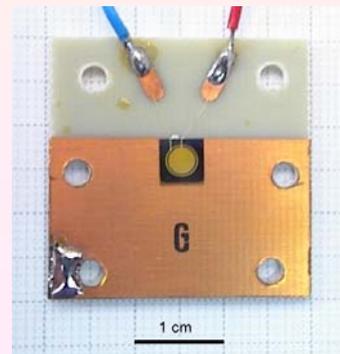
“Measurements should be made between the backside and the central electrode with the guard ring kept at the same potential as the central part (usually grounded)”.

Guard ring at ground, polarization on the backside

“Wherever possible measurements should be performed at a temperature around either 20°C or 0°C”.

Temperature: 19.1 - 21.6 °C

The IV and CV measurements between minimum and maximum bias values should be made both for increasing and decreasing voltages.



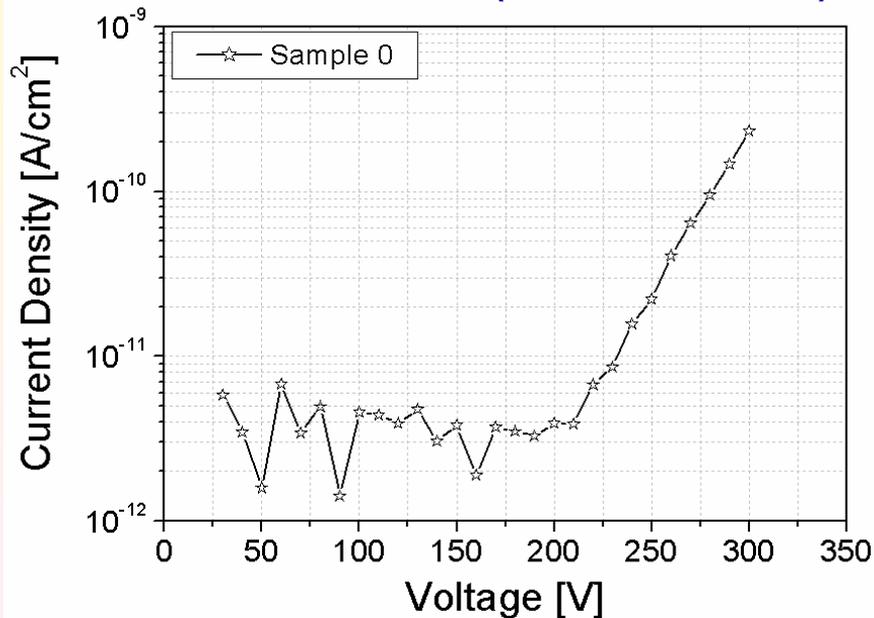
I-V characterization

Reverse bias

For the moment we have characterized: 9 small diodes and 2 large diodes from SMP wafer.

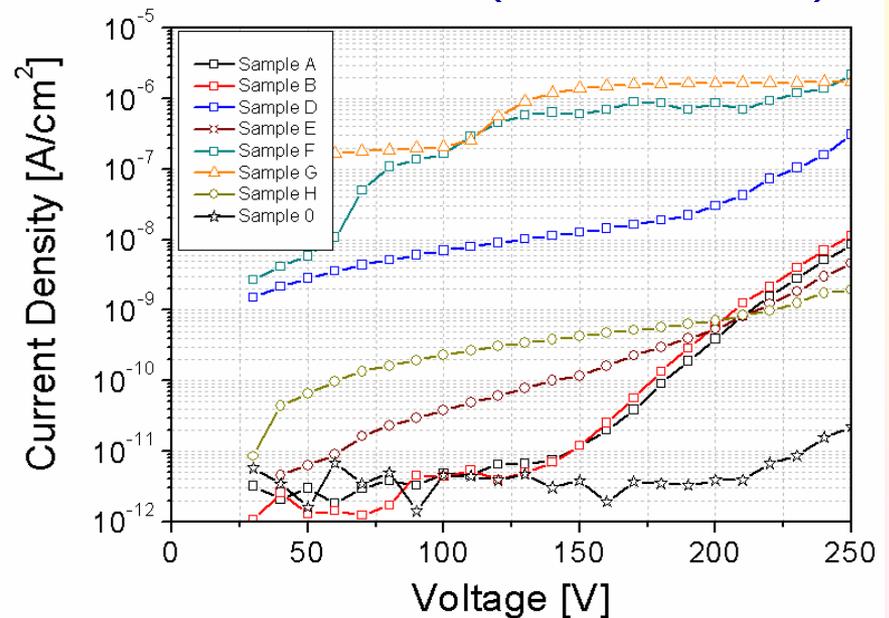
Full depletion at about 200 V - 220 V (from C-V measurements)

V-I Characteristic (7 mm² electrode)



Best result

V-I Characteristic (7 mm² electrode)



All 7 mm² diodes

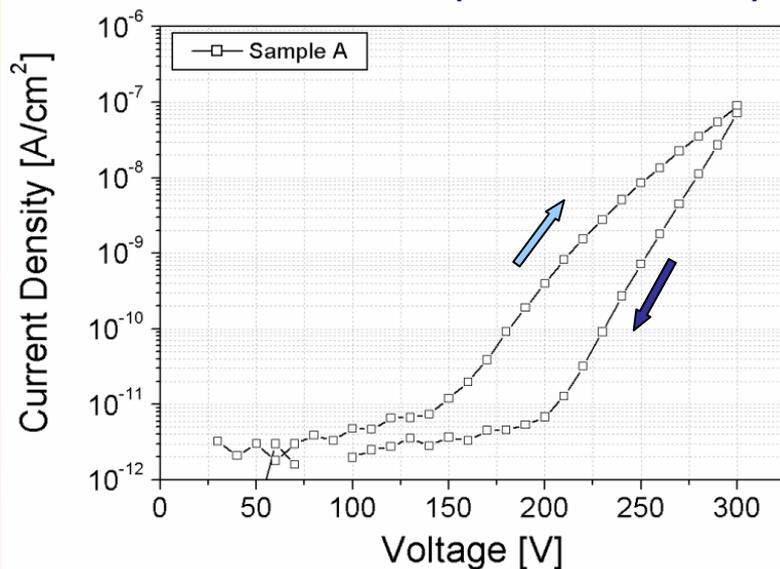
CONDITIONS: increasing voltages; 10 V steps; 10 seconds between two voltages; average on three measurements for every voltage (0.5 s time step).

I-V characterization

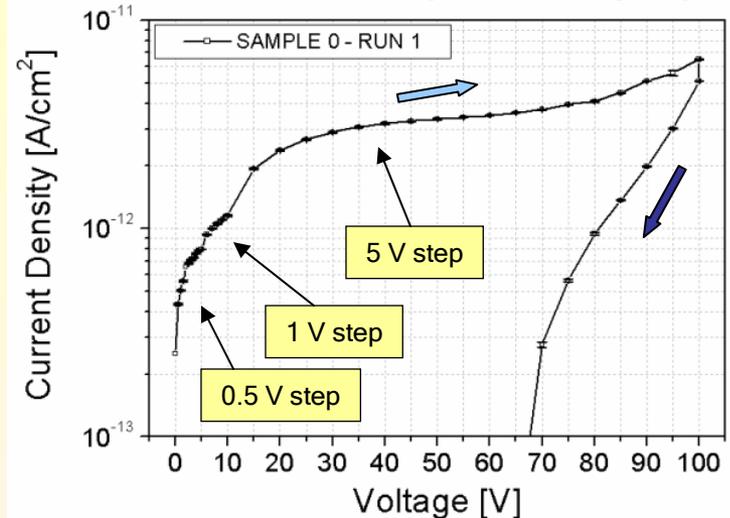
Reverse bias

If the measurements can be made in one direction only (e.g. lack of time) the decreasing bias voltage mode should be preferred, wherever possible, as giving usually more repeatable results. However the measurements with two directions of voltage change are always strongly recommended. In all cases the time of the voltage ramp should be given in the measurement description.

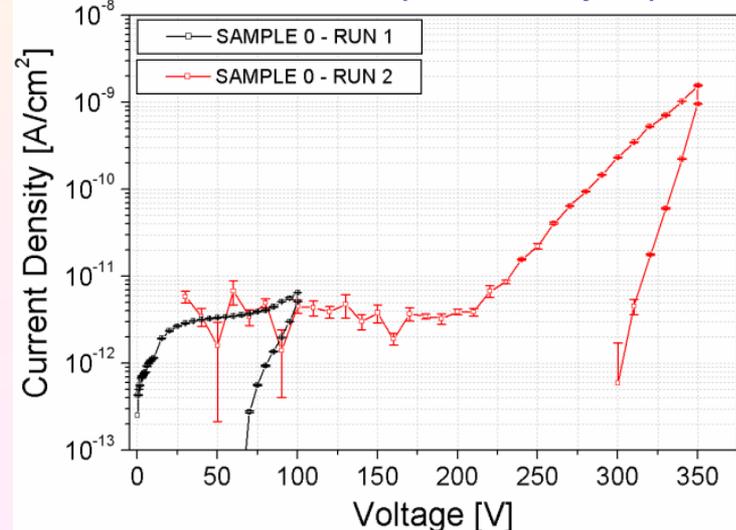
V-I Characteristic (7 mm² electrode)



V-I Characteristic (7 mm² samples)

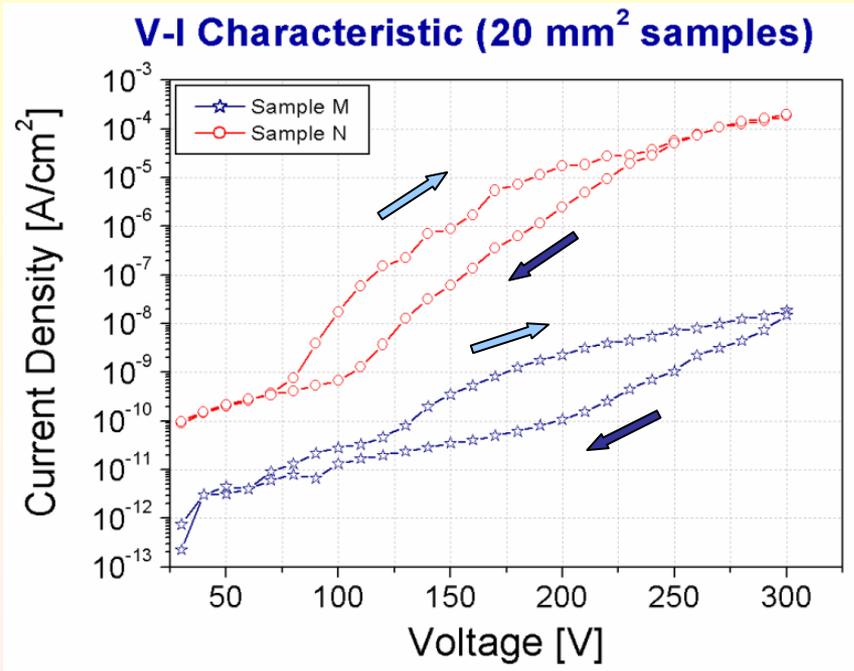
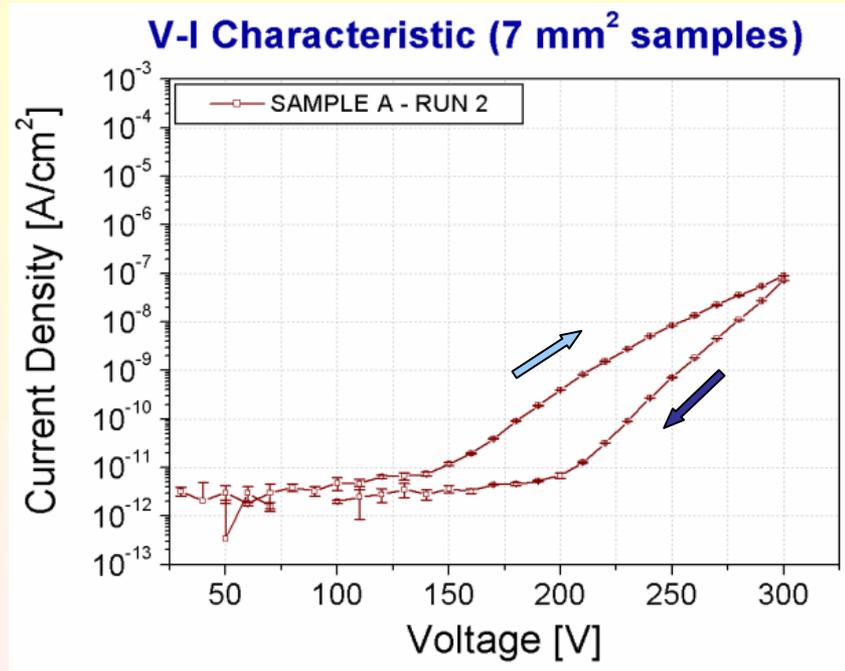


V-I Characteristic (7 mm² samples)



I-V characterization

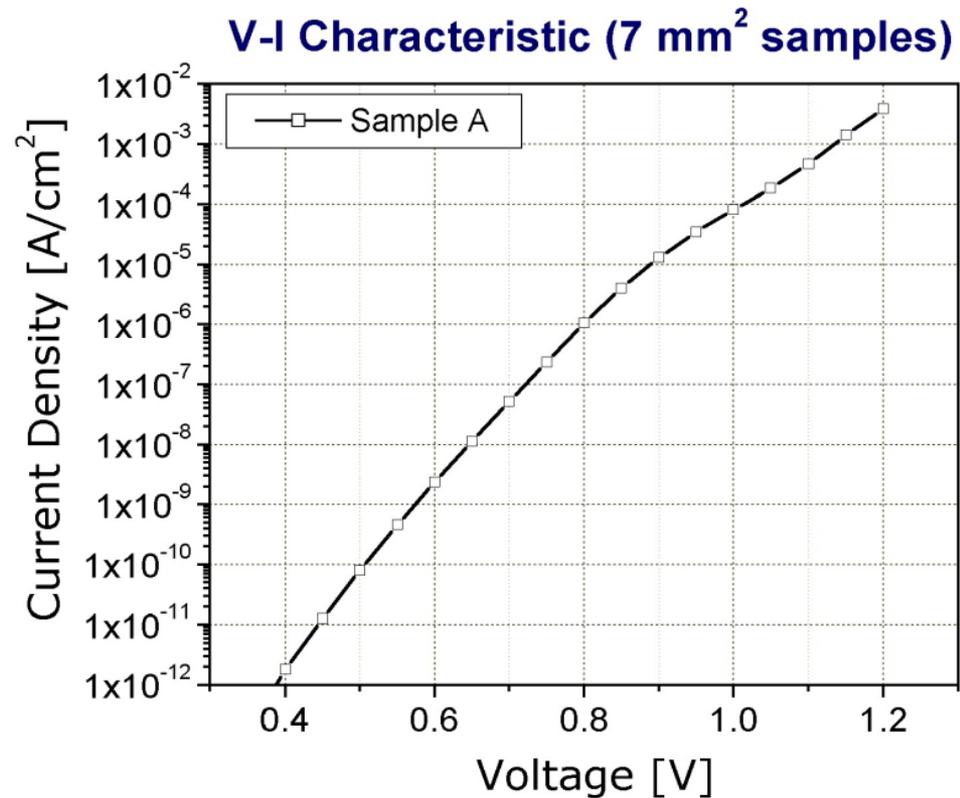
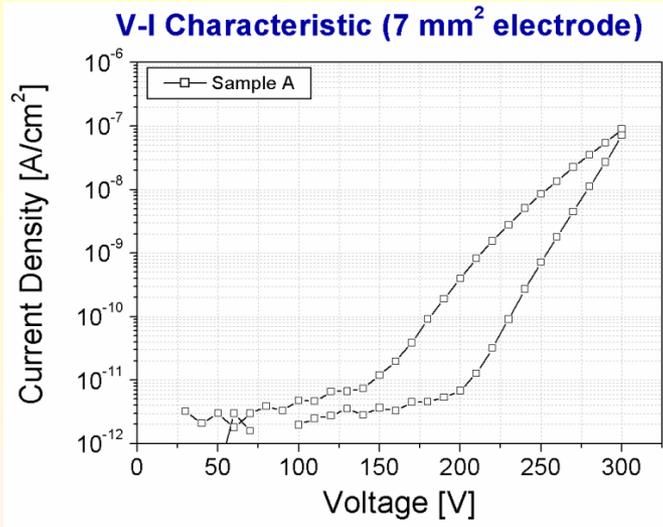
Reverse bias



CONDITIONS: increasing voltages first and decreasing voltages after; 10 V steps; 10 seconds between two voltages;
average of three measurements for every voltage (0.5 s time step).

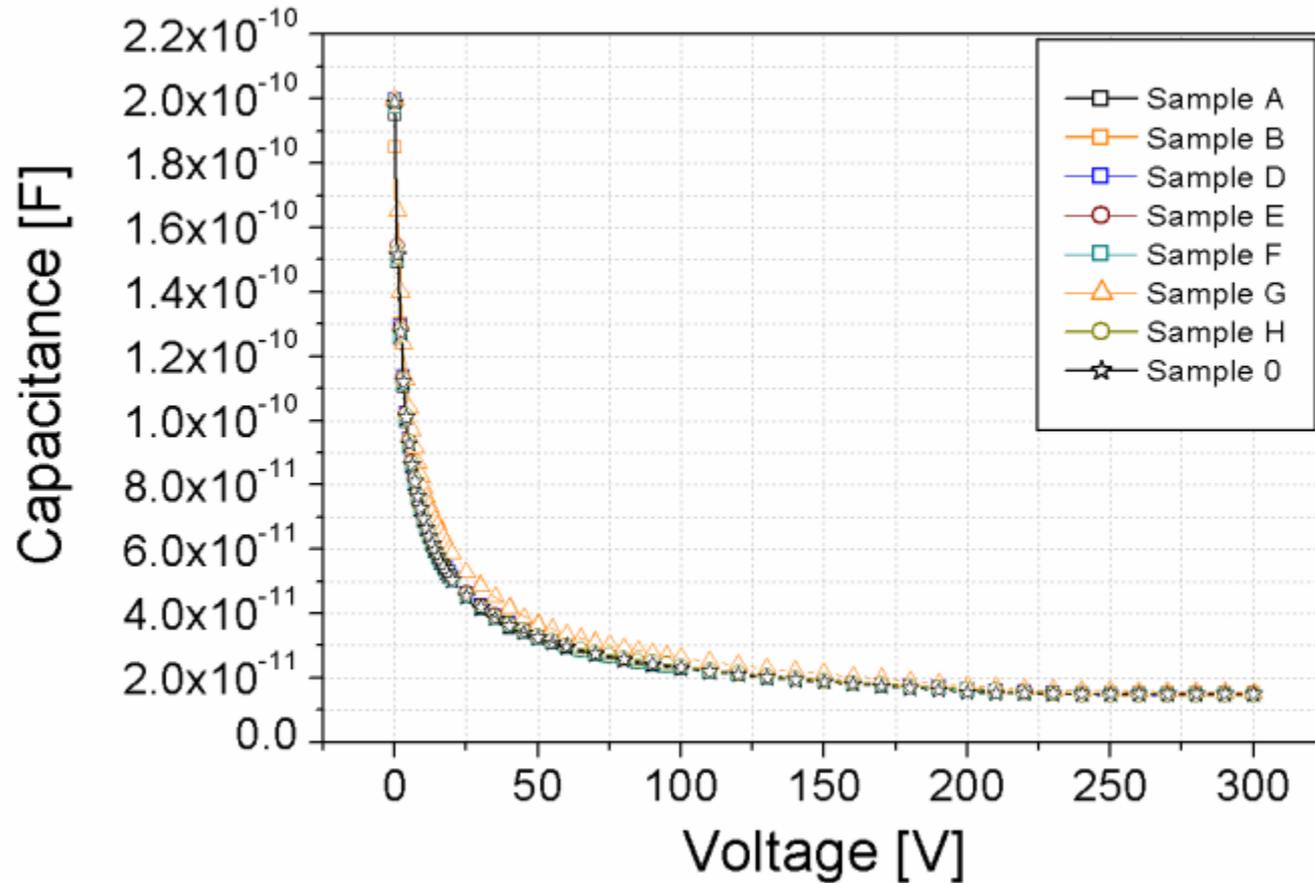
I-V characterization

Forward bias



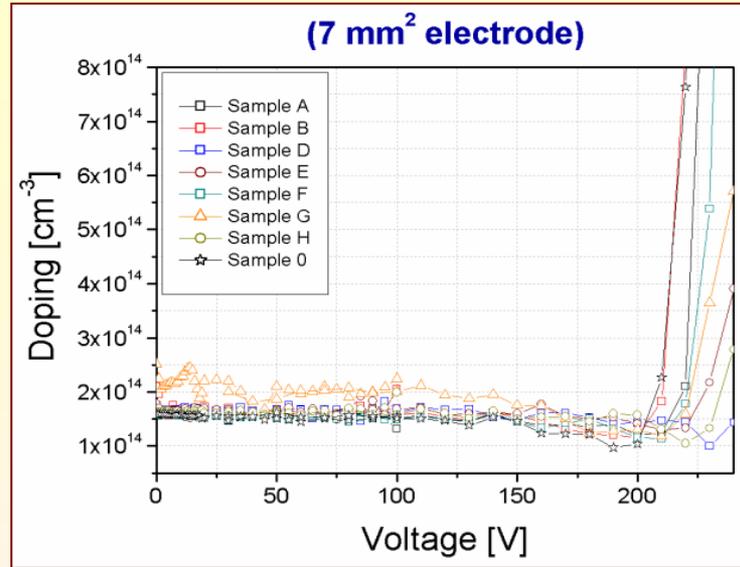
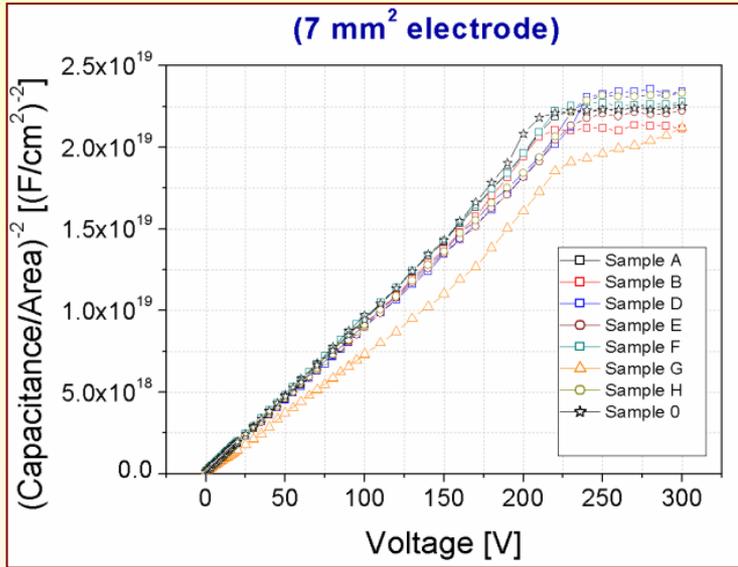
C-V characterization

C-V Characteristic (7 mm² electrode)



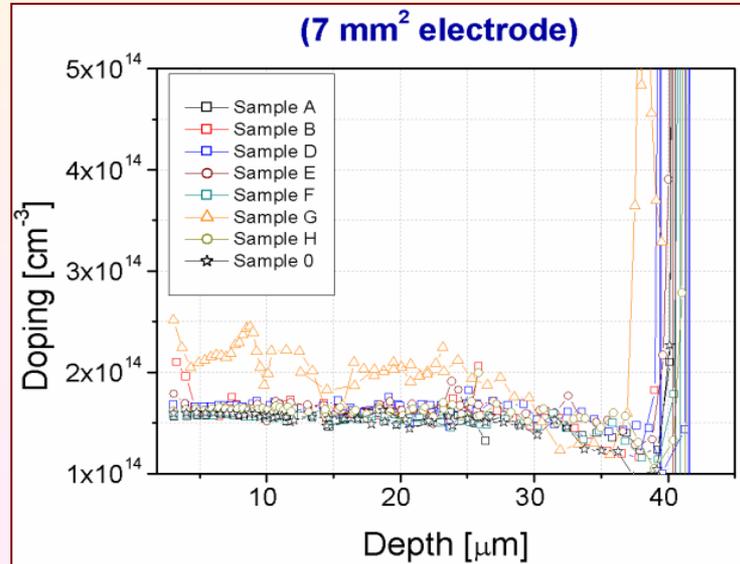
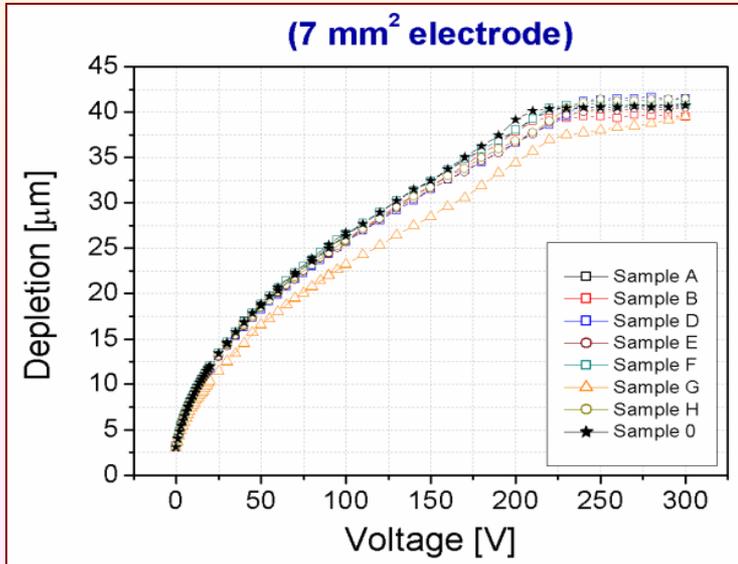
About 15 pF at full depletion voltages

C-V characterization



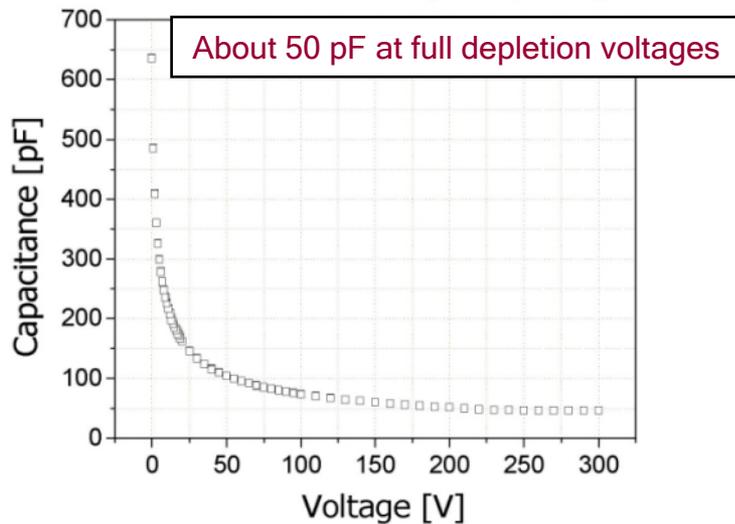
Full depletion
 $\approx 40 \mu\text{m}$

Doping
 $\approx 1.5 \cdot 10^{14} \text{ cm}^{-3}$

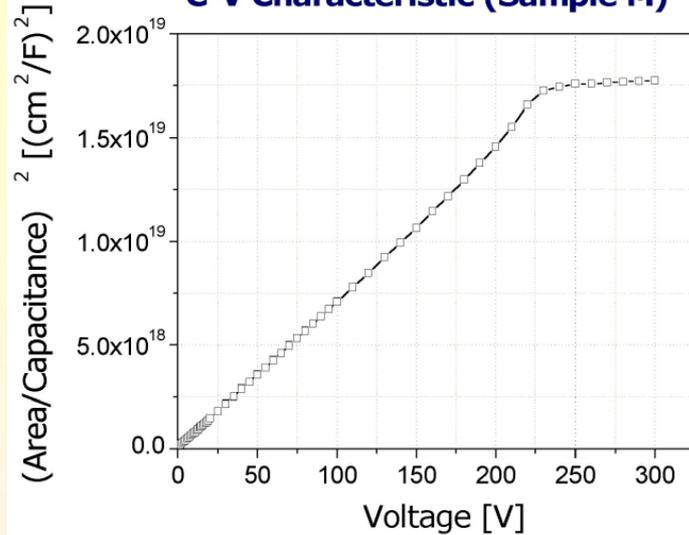


C-V characterization

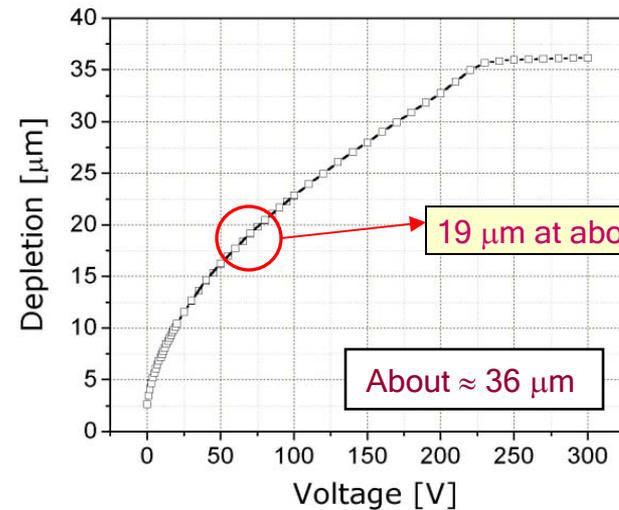
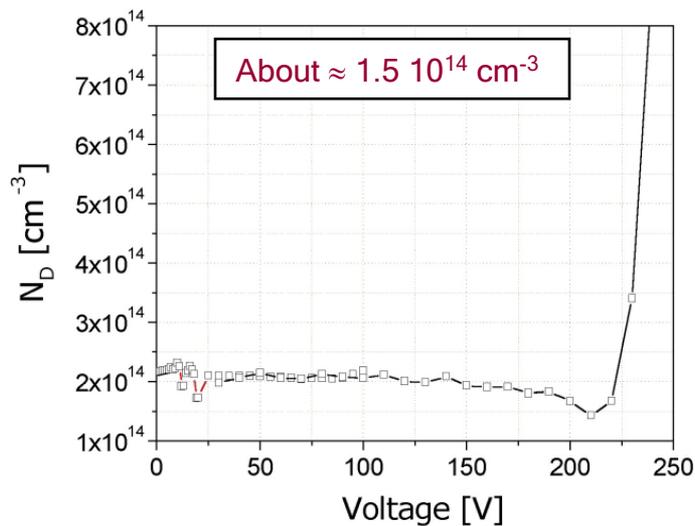
C-V Characteristic (Sample M)



C-V Characteristic (Sample M)



Doping (Sample M)



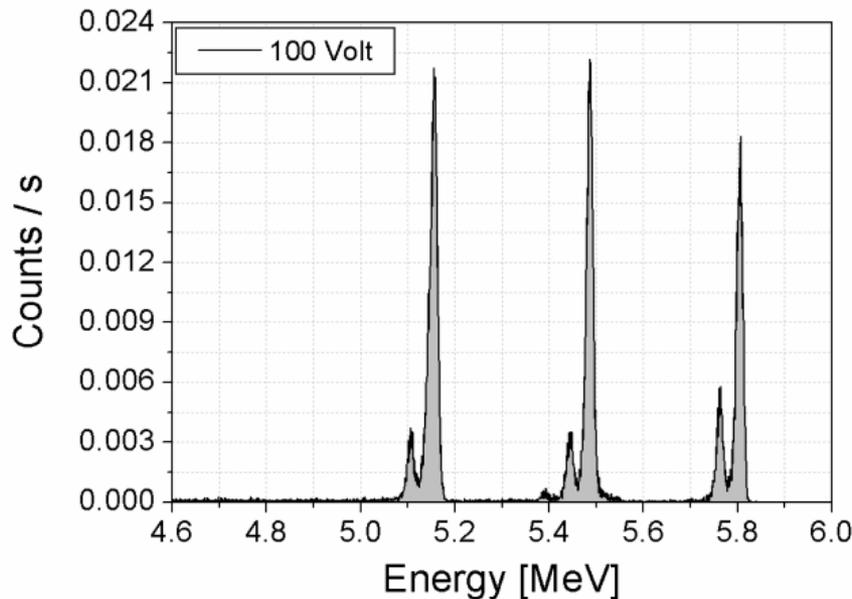
Alpha particle measurements

To perform alpha particle measurements we used a triple ultra-thin window Alpha Source.

Plutonium (^{239}P): Peaks: 5.16 MeV (73.1 %); 5.14 MeV (15.0%); 5.10 MeV (11.8 %); others
Americium (^{241}Am): Peaks: 5.49 MeV (85.2 %); 5.44 MeV (12.8 %); 5.39 MeV (1.4 %); others
Curium (^{244}Cm): Peaks: 5.80 MeV (77.4 %); 5.76 MeV (23.0 %); others

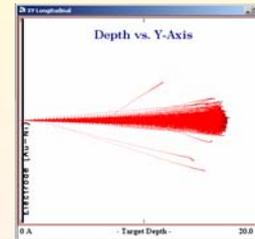
Spectrum obtained using a 25 mm² Si detector and our electronic set-up.

Alpha Particle Measurements (silicon)



Energy Resolution = $\sigma_E = 7 \pm 1$ keV
(Ortec calibration was 6.8 keV)

Penetration in SiC



5.16 MeV → 16.2 μm
5.49 MeV → 17.9 μm
5.80 MeV → 19.4 μm

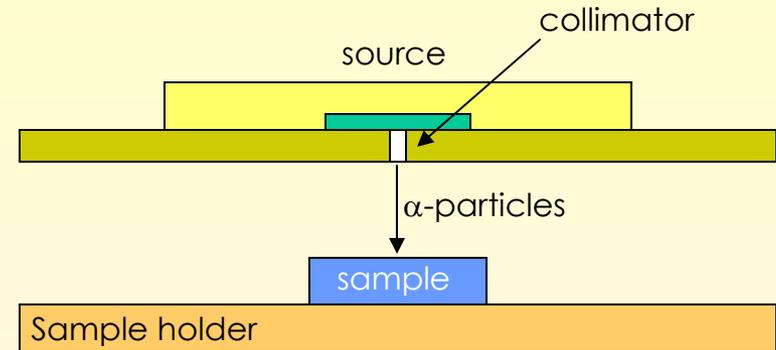
For the moment we have characterized:

2 small diodes from SMP wafer
sample 0
sample B

1 large diode from SMP wafer
sample M

Alpha particle measurements

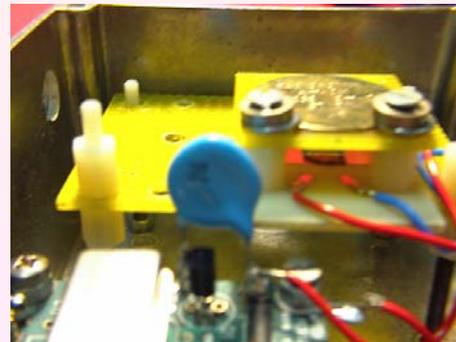
Our set-up



Preamplifier: Amptek A250

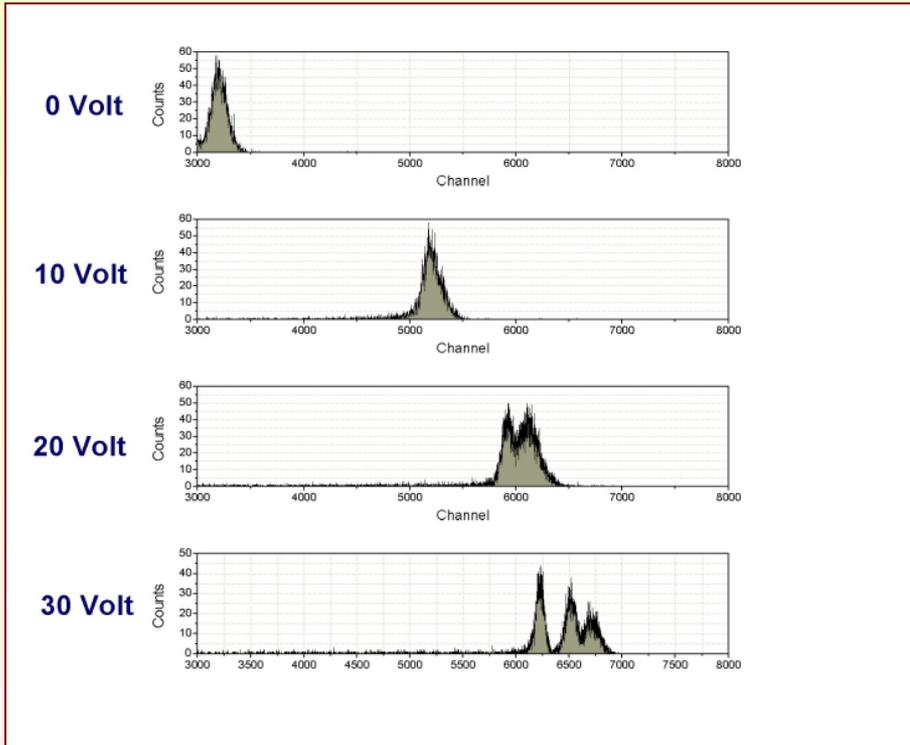
Amplifier & Multichannel: Eagle/Classic
(APTEC-NRC)

Voltage Source: Keithley 617: 0 / +100 Volt
Stanford PS350: +30 / +350 Volt

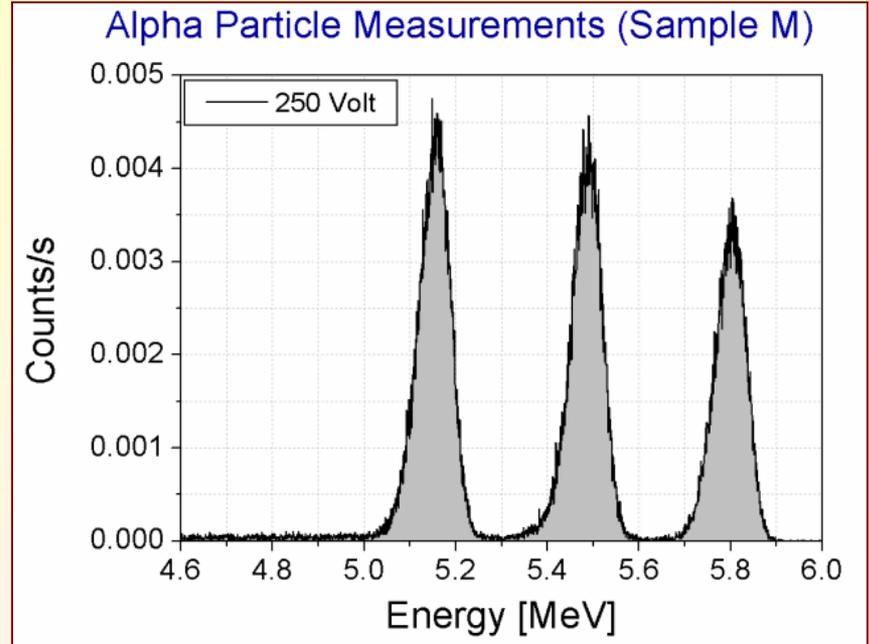


The source-sample-preamplifier box was placed in vacuum.

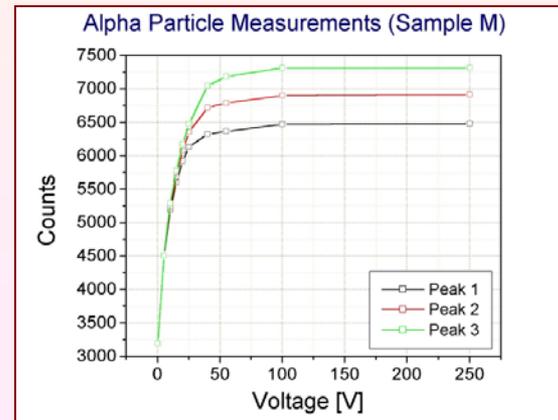
Alpha particle measurements



It was possible to calculate the electron-hole pair creation energy: 7.75 ± 0.13 eV



Energy Resolution = $\sigma_E = 29 \pm 5$ keV



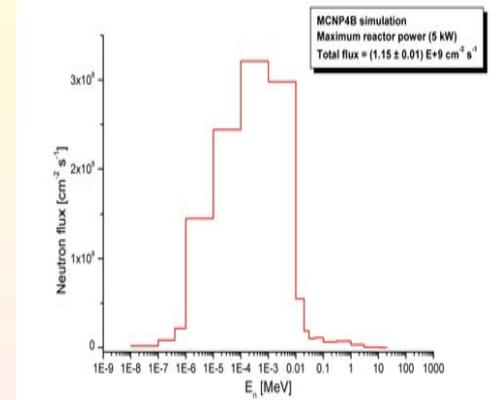
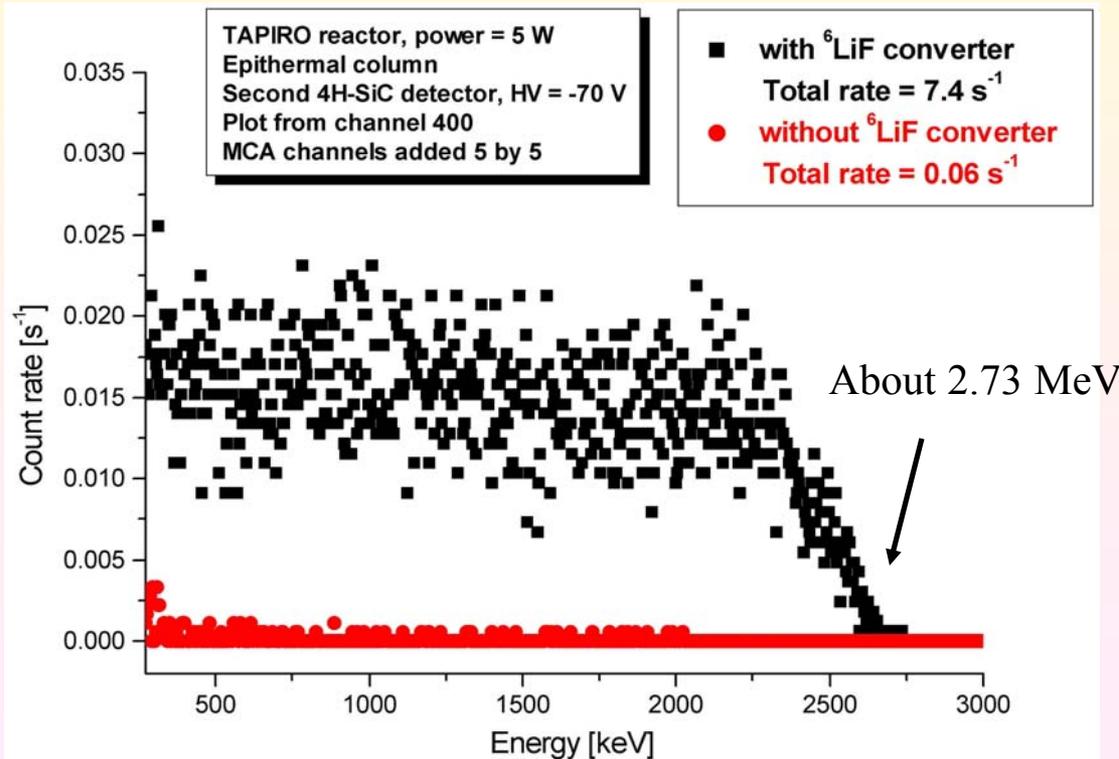
Preliminary neutrons detection measurements

Using an old 1.5 diameter detector

TAPIRO: reactor located at ENEA Casaccia Research Centre, Roma. Epithermal column designed and realized in view of BNCT (Boron Neutron Capture Therapy) treatments (special application: brain tumours)

Total neutron flux @ maximum reactor power (5 kW): $1.15 \cdot 10^9 \text{ cm}^2 \text{ s}^{-1}$.

No significant change in count rate after about 10^{13} neutrons cm^2 .



Conclusions

- We successfully tested a 1.5 diameter SiC Schottky diode as neutron detector. No significant change in count rate after about 10^{13} neutrons cm^2 .
- On purpose we produced large area Schottky SiC diodes (3 mm and 5 mm diameters) suitable for neutrons detection.
- From CV and IV characterizations we measured a full depletion of about 40 μm at about 200V-220V.
- From alpha detection we obtained a good response with an Energy Resolution of $\sigma_E = 29 \pm 5$ keV.